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AMENDMENT TO THE CLAIMS

LISTING OF CLAIMS

- 5 1. (Original) A stain-resist composition comprising:
 - a crosslinking agent comprising at least one polymer having at least two hydroxyl groups; and
 - a stain-resist agent comprising at least one polymer.
- 2. (Original) The stain-resist composition, according to Claim 1, wherein said crosslinking agent is a polybutadiene having at least two hydroxyl groups.
 - 3. (Original) The stain-resist composition of Claim 2, wherein said polybutadiene is hydroxyl-terminated.
 - 4. (Original) The stain-resist composition, according to Claim 2, wherein said polybutadiene is further functionalized with at last one epoxy group.
- 5. (Original) The stain-resist composition of Claim 3, wherein said hydroxyl terminated polybutadiene is grafted with maleic anhydride.
 - 6. (Original) The stain-resist composition of Claim 1, wherein said crosslinking agent contains at least one vinyl group.
- 7. (Currently amended) The stain-resist composition of Claim 1, wherein said stain-resist
 20 agent is a polymer selected from the group consisting of polymethacrylic acid, and
 hydrolyzed maleic anhydride copolymerized with at least one monomer, and mixtures
 thereof.
 - (Original) The stain-resist composition of Claim 7, wherein the number average molecular weight of said polymethacrylic acid is at least 300,000.
- 9. (Currently amended) The stain-resist composition, according to Claim 7, wherein said at least one monomer is selected from the group consisting of α-olefins and styrenes.
 - 10. (Original) The stain-resist composition of Claim 9, wherein said alpha-olefin is octene.
 - 11. (Currently amended) The stain-resist composition, according to Claim 7, wherein up to 70 mole % of said maleic anhydride may be replaced by a monomer selected from the

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group consisting of acrylic acid, methacrylic acid, itaconic acid, vinyl sulfonic acid, vinyl phosphonic acid, styrene sulfonic acid, alkyl (C_{1-4}), acrylate, alkyl (C_{1-4}) methacrylate, vinyl acetate, vinyl chloride, vinylidine chloride, vinyl sulfides, N-vinyl pyrrrolidone pyrrolidone, acrylonitrile, acrylamide, and mixtures thereof.

- 5 12. (Original) The stain-resist composition of Claim 1, wherein said stain-resist agent further comprises a sulfonated phenol-formaldehyde condensation product.
 - (Original) The stain-resist composition of Claim 1, further comprising a pH-adjusting agent.
- 14. (Original) The stain-resist composition of Claim 13, wherein said agent adjusts the pH to from about 1 to about 8.
 - 15. (Original) The stain-resist composition of Claim 13, wherein said agent adjusts the pH to from about 3 to about 4.
 - 16. (Original) A process for imparting resistance to staining by coffee and/or acid dyes to a polyamide substrate, the process comprising contacting said polyamide substrate with a stain-resist composition comprising:
 - a crosslinking agent comprising at least one polymer having at least two hydroxyl groups; and
 - a stain-resist agent comprising at least one polymer.
- 17. (Original) The process for imparting resistance to staining by coffee and/or acid dyes to a polyamide substrate, according to Claim 16, wherein said crosslinking agent is a polybutadiene having at least two hydroxyl groups.
 - 18. (Original) The process for imparting resistance to staining by coffee and/or acid dyes to a polyamide substrate, according to Claim 17, wherein said hydroxyl groups are terminal to said polybutadiene.
- 19. (Original) The process for imparting resistance to staining by coffee and/or acid dyes to a polyamide substrate, according to Claim 17, wherein said polybutadiene is further functionalized with at least one epoxy group.
 - 20. (Original) The process for imparting resistance to staining by coffee and/or acid dyes to a polyamide substrate, according to Claim 16, wherein said crosslinking agent contains at least one vinyl group.

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- 21. (Original) The process for imparting resistance to staining by coffee and/or acid dyes to a polyamide substrate, according to Claim 18, wherein said hydroxyl-terminated polybutadiene is grafted with maleic anhydride.
- 22. (Original) The process for imparting resistance to staining by coffee and/or acid dyes to a polyamide substrate, according to Claim 16, wherein said stain-resist agent is a polymer selected from the group consisting of polymathacrylic acid and hydrolyzed maleic anhydride copolymerized with at least one monomer, and mixtures thereof.
- 23. (Original) The process for imparting resistance to staining by coffee and/or acid dyes to a polyamide substrate, according to Claim 16, wherein the number average molecular weight of said polymethacrylic acid is at least 300,000.
- 24. (Original) The process for imparting resistance to staining by coffee and/or acid dyes to a polyamide substrate, according to Claim 22, wherein said monomer is selected from the group consisting of α -olefins and styrenes.
- 25. (Original) The process for imparting resistance to staining by coffee and/or acid dyes to a polyamide substrate, according to Claim 24, wherein said alpha-olefin is octene.
- 26. (Currently amended) The process for imparting resistance to staining by coffee and/or acid dyes to a polyamide substrate, according to Claim 22, wherein up to 70 mole % of said maleic anhydride may be replaced by a monomer selected from the group consisting of acrylic acid, methacrylic acid, itaconic acid, vinyl sulfonic acid, vinyl phosphonic acid, styrene sulfonic acid, alkyl (C₁₋₄) accrylate, alkyl (C₁₋₄) methacrylate, vinyl acetate, vinyl chloride, vinylidine chloride, vinyl sulfides, N-vinyl pyrrolidone, acrylamide, and mixtures thereof.
- 27. (Original) The process for imparting resistance to staining by coffee and/or acid dyes to a polyamide substrate, according to Claim 16, wherein said stain-resist composition further comprises a sulfonated phenol-formaldehyde condensation product.
- 28. (Original) The process for imparting resistance to staining by coffee and/or acid dyes to a polyamide substrate, according to Claim 16, wherein said stain-resist composition further comprising a pH-adjusting agent.

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- 29. (Original) The process for imparting resistance to staining by coffee and/or acid dyes to a polyamide substrate, according to Claim 28, wherein said agent adjusts the pH to from about 1 to about 8.
- 30. (Original) The process for imparting resistance to staining by coffee and/or acid dyes to a polyamide substrate, according to Claim 28, wherein said agent adjusts the pH to from about 3 to about 4.
 - 31. (Original) The process for imparting resistance to staining by coffee and/or acid dyes to a polyamide substrate, according to Claim 16, further comprising drying.
- 32. (Original) The process for imparting resistance to staining by coffee and/or acid dyes to a polyamide substrate, according to Claim 31, wherein said drying is carried out at temperature of from about 100° to about 190°C.
 - 33. (Original) The process for imparting resistance to staining by coffee and/or acid dyes to a polyamide substrate, according to Claim 31, wherein said drying is carried out at temperature of from about 130° to about 150°C.
- 15 34. 38. (Canceled)